

U.S. Department of Commerce, Patent and Trademark INFORMATION DISCLOSURE STATEMENT BY APPLICANT SEP 04 2003 (Use several sheets if necessary)	Atty. Docket No.	Application No.
	TNCR.196US0	09/833,084
	Applicant(s)	
	Abdulhalim et al.	
	Filing Date	Group
	4/10/01	1775

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*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
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	2	5,607,818	3/4/97	Akram et al.			
	3	5,738,961	4/14/98	Chen et al.			
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							Translation	
		Document	Date	Country	Class	Subclass	Yes	No

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28	6	Copy of International Search Report, mailed 9/18/02.

Examiner

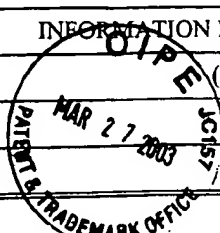
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9/4/03

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	Ibrahim Abdulhalim, et al.	8866
	Filing Date	Group
	April 10, 2001	1775



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B6	WO 02/25708 A2	3/28/02	KLA-Tencor Corporation		
B7	WO 02/25723 A2	3/28/02	Nova Measuring Instruments, Ltd.		
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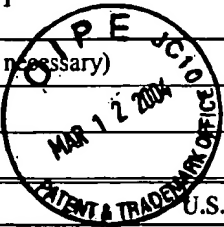
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	AH							
	AI							
	AJ							
	AK							
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							Translation	
	Document	Date	Country	Class	Subclass	Yes	No	
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(Use several sheets if necessary)		Ibrahim Abdulhalim, et al.		8866	
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Foreign Patent Documents								
							Translation	
		Document	Date	Country	Class	Subclass	Yes	No

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)		

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							Translation
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